

10. (amended) A method as claimed in claim 1, wherein the metallic layer comprises copper or silver.

11. (amended) A method as claimed in claim 1, wherein the transparent conductor layer is pretreated before plating.

12. (amended) A method as claimed in claim 1, wherein the transparent conductor layer comprises a conductive oxide.

15. (amended) A method as claimed in claim 1, wherein the gate conductor (42) is deposited and patterned with a first lithographic process and the transparent conductor layer defining source and drain conductors (28,30) and pixel electrodes (38) is deposited and patterned with a second lithographic process, the silicon layer being self aligned to the gate conductor.

16. (amended) A method as claimed in claim 1 for forming the active plate of an active matrix liquid crystal display.

19. (amended) A device as claimed in claim 17, comprising:

a gate conductor layer (40) over an insulating substrate defining the gate conductors and also defining row conductors;